

Notice of References Cited	Application/Control No. 09/893,340	Applicant(s)/Patent Under Reexamination KANG ET AL.	
	Examiner Erik Kielin	Art Unit 2813	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-4,530,149	07-1985	Jastrzebski et al.	438/156
	B	US-5,141,878	08-1992	Benton et al.	257/461
	C	US-6,251,754	06-2001	Ohshima et al.	438/406
	D	US-6,274,464	08-2001	Drobny et al.	438/507
	E	US-6,342,436	01-2002	Takizawa, Ritsuo	438/473
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
	U	Moriceau et al. "Hydrogen annealing treatment used to obtain high quality SOI surfaces" IEEE International SOI Conference, October 1998, pp. 37-38.			
	V	Tate et al. ("Defect Reduction of Bonded SOI Wafers by Post Anneal Process in H2 Ambient" IEEE International SOI Conference Proceedings, 5-8 October 1998, pp. 141-142.			
	W	Merriam Webster's Collegiate Dictionary, 10th ed., p. 388. <i>1998</i> ^			
	X				

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.